

MICROCOPY RESOLUTION TEST CHART

AD A 138241

SELECTE FEB 2 7 1984

This report was submitted by The Asrospace Corporation, El Segundo, CA 90245, under Contract No. F04701-83-C-9084 with the Space Division, P.O. Box 92960, Worldway Postal Center, Los Angeles, CA 90009. It was reviewed and approved for The Aerospace Corporation by S. Feuerstein, Director, Chemistry and Physics Laboratory. 1st Lt Robert J. Peters, SD/TGJ, was the project officer for the Mission Oriented Investigation and Experimentation (MOIE) Program.

This report has been reviewed by the Public Affairs Office (PAS) and is releasable to the National Technical Information Service (NTIS). At HTIS, it will be available to the general public, including foreign nationals.

This technical report has been reviewed and is approved for publication. Publication of this report does not constitute Air Force approval of the report's findings or conclusions. It is published only for the exchange and stimulation of ideas.

Project Officer

GH-15, Director West Commt Office, Air Force Space Technology Center

## Unclassified

SECURITY CLASSIFICATION OF THIS PAGE (Then Date Entered)

REPORT DOCUMENTATION PAGE		READ INSTRUCTIONS BEFORE COMPLETING FORM	
1. REPORT HUMBER	1	3. RECIPIENT'S CATALOG NUMBER	
SD-TR-83-88	AD-A138241		
4. TITLE (and Subtitle)	,	S. TYPE OF REPORT & PERIOD COVERED	
Calculation of Misfit Dislocation	ons	ļ	
and Dangling Bond Densities in Abrupt Hg <sub>1-x</sub> Cd <sub>x</sub> Te Heterojunction		6. PERFORMING ORG. REPORT NUMBER	
7. AUTHOR(a)	18	TR-0084(4945-07)-I	
7. AUTHOR(2) Richard B. Schoolar	· · · · · · · · · · · · · · · · · · ·		
	, , , , , , , , , , , , , , , , , , ,	F04701-83-C-0084	
A AMB AND ARREST	- <u></u>	TARK TARK	
5. PERFORMING ORGANIZATION NAME AND ADDRESS The Aerospace Corporation	<i>§</i>	10. PROGRAM ELEMENT, PROJECT, TASK AREA & WORK UNIT NUMBERS	
El Segundo, Calif. 90245	,	}	
	· · · · · · · · · · · · · · · · · · ·	<u> </u>	
11. CONTROLLING OFFICE NAME AND ADDRESS Space Division		12. REPORT DATE	
Los Angeles Air Force Station	,	15 December 1983	
Los Angeles, Calif. 90009		6	
14. MONITORING AGENCY NAME & ADDRESS(If differen	at from Controlling Office)	18. SECURITY CLASS. (of this report)	
	,	Unclassified	
	!	ISA. DECLASSIFICATION/DOWNGRADING	
16. DISTRIBUTION STATEMENT (of this Report)		SCHEDULE	
Approved for public release; distribution unlimited.			
17. DISTRIBUTION STATEMENT (of the obstract entered	In Block 20, if different free	a Report)	
	and the second s		
(10+0+he 11th Powersq.cm) X Sub1-XSub2) Greater than			
19. KEY WORDS (Continue on reverse side if necessary an	nd identify by block number)	,	
Epitaxial growth HgCdTe Infrared detectors  Interfaces Mercury cadmium telluride			
20. ABSTRACT (Canthus en roverse side II absencery and	\		
Based on the classical theory of epitaxial crystal growth, the misfit dislocations and dangling bond densities of abrupt (11) Hg/LCdTe heterojunctions have been calculated. For the case where $(x_2-x_1) \neq 0.1$ the dangling bond density is on the order of $10^{11}$ cm <sup>-2</sup> . Such large dangling bond densities may produce high interface recombination velocities or band-bending at the interface.			

DO FORM 1478

Unclassified

MENETY CLAMPICATION OF THE PARE (then Dote Brising)

The mercury-cadmium-telluride  $(\mathrm{Hg_{1-x}Cd_xTe})$  alloy system has become an important semiconductor material for fabrication of infrared detectors. A liquid-phase-epitaxy (LPE) technique is commonly used to grow this semiconductor with the desired Cd content on CdTe substrates. This alloy layer-substrate combination has been referred to as a "lattice matched" system since the lattice constants of HgTe and CdTe differ by only 0.3%. The high performance of p-n junction photovoltaic detectors produced from these epitaxial layers has been taken as evidence of low surface recombination velocities and low defect densities at the  $\mathrm{Hg_{1-x}Cd_xTe/CdTe}$  interface.\frac{1}{2} Consequently, interest has been shown for using LPE techniques to produce more complex double-layer heterojunctions for device applications.\frac{2}{2} These structures are comprised of an n-type layer of composition  $x_2$  on a p-type layer of composition  $x_1$  and, in theory, should have lower leakage currents than p-n homojunction photodiodes. However, the defect structure of  $\mathrm{Hg_{1-x}Cd_xTe}$  heterojunctions has not been established.

The purpose of this report is to present calculations of the misfit dislocation and dangling bond densities at abrupt  $\mathrm{Hg}_{1-\mathrm{X}_1}\mathrm{Cd}_{\mathrm{X}_1}\mathrm{Te}/\mathrm{Hg}_{1-\mathrm{X}_2}\mathrm{Cd}_{\mathrm{X}_2}$  the heterojunctions where  $\Delta \mathrm{x} = (\mathrm{x}_2 - \mathrm{x}_1)$  is a variable. The  $\mathrm{Hg}_{1-\mathrm{X}}\mathrm{Cd}_{\mathrm{X}}\mathrm{Te}/\mathrm{Cd}\mathrm{Te}^2$  interface is a special case with the variable  $\Delta \mathrm{x}$  becoming (1-x). The calculations are made for the (111) plane using the theoretical treatment of Oldham and Milnes. According to this study, the misfit dislocations for (111) heterojunctions may lie in the <011>, <101>, and <110> directions with spacing h between sets as shown in Fig. 1. For pure edge dislocations, h is given by

$$h = \frac{3a_1 a_2^2}{\sqrt{2}(a_2^2 - a_1^2)}, a_2 > a_1$$

where  $a_1$  and  $a_2$  are the lattice spacing for  $x_1$  and  $x_2$ , respectively, on both sides of the heterojunction. The interface dangling bond density  $\Delta Ns$  is then

Ms = 3



,	-\A&I	
DTIC	TAB	To .
	ounced	
Justi	fication	
Ву		
Distr	ibution/	
Avai	lability	
	Avail an	d/or
Dist	Specia	1
	1	
14. /		
M'I	1 1	
T		

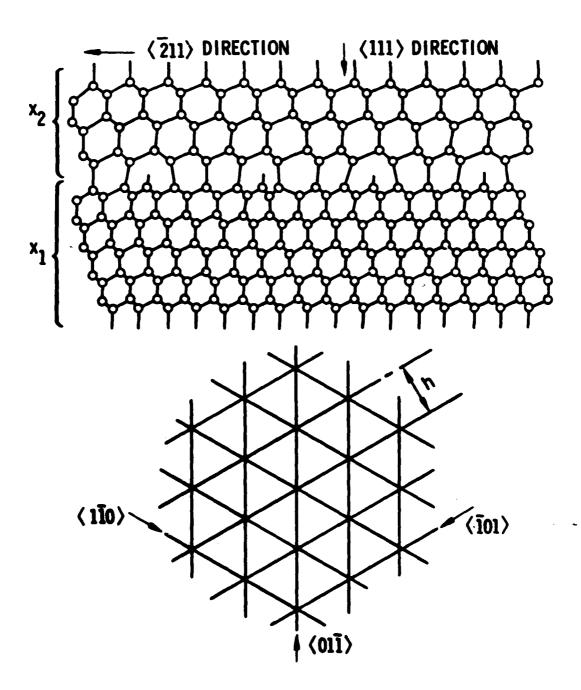


Figure 2. Hisfit Dislocation Lines in the (111) Plane of an Abrupt  $\mathbf{H}_{\mathbf{S}_{1}\dots\mathbf{C}}\mathbf{C}_{\mathbf{x}}\mathbf{T}\mathbf{e}$  Heterojunction. The spacing h is computed from the lattice constants  $\mathbf{a}_{1}$  and  $\mathbf{a}_{2}$  on both sides of the interface.

where c is the mean spacing between bonds along the dislocation line and for (111) orientations is given by

$$c = \frac{a_1 \sqrt{3}}{2\sqrt{2}}$$

A recent study of  $\mathrm{Hg_{1-x}Cd_xTe}$  epitaxial crystal growth<sup>4</sup> has shown that mirror-smooth films can be obtained on  $\mathrm{Hg_{1-x}Cd_xTe}$  substrates when  $\Delta x < 0.03$ . Networks of dislocation lines similar to the ones shown in Fig. 1 were observed when  $\Delta x > 0.07$ .

According to the literature, the lattice constants of CdTe and HgTe at room temperature are 6.4818A and 6.4620A, respectively. The lattice parameter of  $\mathrm{Hg_{1-x}Cd_{x}Te}$  varies approximately linearly with x across the entire composition range. The linear thermal expansion coefficients for both materials is  $5.0 \times 10^{-6}\mathrm{C^{-1}}$  above 300 K.6,7

The dislocation line spacing and dangling bond densities for abrupt (111)  $\mathrm{Hg}_{1-\mathrm{x}}\mathrm{Cd}_{\mathrm{x}}\mathrm{Te}$  heterojunctions are shown in Fig. 2 as a function of  $\Delta \mathrm{x}$ . Since the thermal expansion coefficients of CdTe and HgTe are identical, these calculations apply for all LPE growth temperatures.

These dangling bonds should occur in the  $\mathrm{Hg}_{1-x}\mathrm{Cd}_x\mathrm{Te}$  epitaxial layer and not in the CdTe substrate since the alloy has the smaller lattice constant. In the case of heterojunctions between two alloy semiconductors, the dangling bonds should occur in the layer with the smaller lattice constant which also has the smaller energy gap. It is well established that such dangling bonds can generate either donor-like or acceptor-like interface states, recombination centers, traps, or in rare instances may remain neutral. The interfacial barrier height generated by donor or acceptor-like states can be estimated from ANs following the method outlined by Many, Goldstein, and Grover for calculating surface potential. According to these calculations, barrier heights in excess of 4 KT/q can be generated whenever  $\Delta x > 0.1$ .

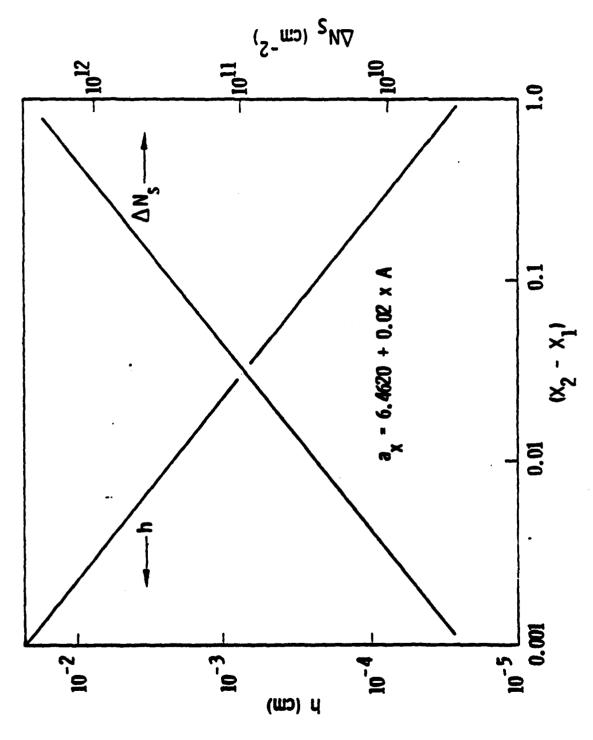


Figure 2. Dislocation Line Spacing h and Dangling Bond Density  $\Delta N_B$  in Abrupt (111)  $Hg_{1-\chi}Cd_{\chi}Te$  Heterojunctions where Compositions on Both Sides of the Interface are  $x_1$  and  $x_2$ .

According to this calculation, the  $\mathrm{Hg}_{1-x}\mathrm{Cd}_x\mathrm{Te}/\mathrm{CdTe}$  interface is far from ideal when  $\Delta x > 0.1$ . For values of  $\Delta x$  typically encountered in epitaxial growth of detector layers,  $\Delta Ns > 10^{12}\,\mathrm{cm}^{-2}$ . Such high densities of dangling bonds could easily give rise to high interface state densities and cause severe minority carrier recombination. Of course these interface states may produce band-bending of the proper sign to screen minority carriers from the CdTe interface. This screening could reduce the interface recombination velocity and produce the enhanced "limited volume" diode characteristics reported for p-n junctions fabricated in  $\mathrm{Hg}_{1-x}\mathrm{Cd}_x\mathrm{Te}$  epitaxial layers. 1

In the case of double layer heterojunctions with coincident metallurgical and p-n junctions, the interface states would occur in the depletion region and could produce high recombination rates and excess leakage currents. Any band-bending which would screen thermally generated carriers would also repel optically generated carriers and degrade detector quantum efficiency. Thus,  $Hg_{1-x}Cd_xTe$  heterojunctions with  $\Delta x > 0.1$  might be expected to exhibit poor photodiode characteristics.

I conclude that abrupt  $\mathrm{Hg_{1-x}Cd_xTe}$  heterojunction interfaces should have misfit dislocations and dangling bond densities in excess of  $10^{11}$  cm<sup>-2</sup> whenever  $\Delta x > 0.10$ . Such large numbers of dangling bonds may cause severe minority carrier recombination and/or band-bending at the interface. Thus, these interfacial defects may play an important role, or may even dominate heterojunction device characteristics.

## References

- 1. M. Lanir, C.C. Wang, and A.H.B. Vanderwyck, Appl. Phys. Lett. <u>34</u>, 50 (1979).
- 2. S.H. Shin, A.H.B. Vanderwyck, J.C. Kim, and D.T. Cheung, Appl. Phys. Lett. 37, 402 (1980).
- 3. W.G. Oldham and A.G. Milnes, Solid-State Electron. 7, 153 (1964).
- 4. Y. Nemirousky, S. Margalit, E. Finkman, Y. Shacham Damand, and I. Kidron, J. Electron, Mater. 11, 133 (1982).
- 5. J.C. Woolley and B. Ray, J. Phys. Chem. Solids 13, 151 (1960).
- Novikova, Fiz. Tverd. Tela 3, 178 (1961) Eng. Trans.: Soviet Phys. Solid State 3, 129 (1961).
- 7. Novikova, and N. Kh. Abrikosov, Fiz. Tverd. Tela 5, 2138 (1963) Eng.

  Trans.:Soviet Phys. Solid State 5, 1558 (1964).
- 8. A. Many, Y. Goldstein, and N.B. Grover, <u>Semiconductor Surfaces</u>, Chapter 4

  (North Holland Publishing Company, Amsterdam, 1965).

